

Title (en)
UV-RESISTANT ELECTRODE ASSEMBLY

Title (de)
UV-BESTÄNDIGE ELEKTRODENANORDNUNG

Title (fr)
ENSEMBLE ÉLECTRODE RÉSISTANT AUX UV

Publication
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Application
EP 16206478 A 20161222

Priority
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Abstract (en)
The present invention is therefore to an electrode assembly comprising at least a substrate, a conductive layer formed on the substrate; said conductive layer comprising at least a metal nanowires, and an overcoat layer formed on the conductive layer; said overcoat layer comprising at least a matrix, wherein the conductive layer and/or the overcoat layer comprises at least a \dot{A} -conjugated conductive polymer. The invention also concerns a method for production of said electrode assembly and electronic devices comprising said electrode assembly.

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CPC (source: EP)
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Citation (applicant)
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